

MOSFET (Metal Oxide Semiconductor Field Effect Transistor)

MOSFETs are basically of 2 types:

1. Depletion Type MOSFET
2. Enhancement Type MOSFET

MOSFET basically has 4 terminals:

1. Source (S)
2. Drain (D)
3. Gate (G)
4. Body (B)

Depletion type MOSFET:

There is a physical channel between S & D. No ~~sep~~ separation between S & D

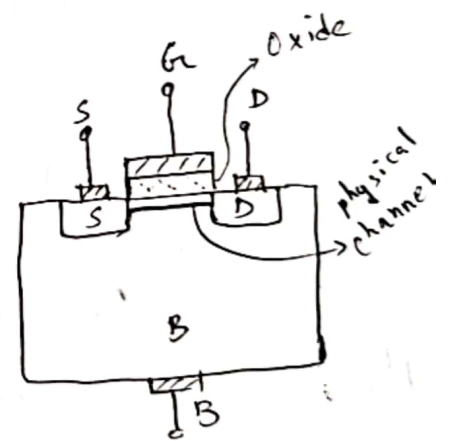


Fig: Depletion type MOSFET

Enhancement type MOSFET:

There is no physical channel between S & D. Channel has to be created by applying proper biasing voltage between gate (G) and source (S).

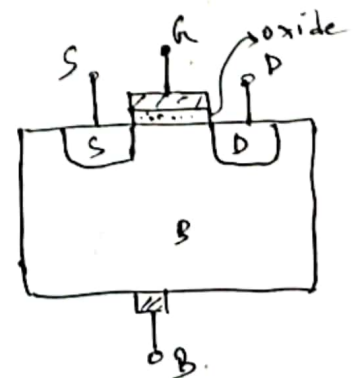


Fig: Enhancement type MOSFET

Both Depletion type MOSFET and Enhancement type MOSFET can be categorized either as n-channel MOSFET (nmos) or p-channel MOSFET (pmos).

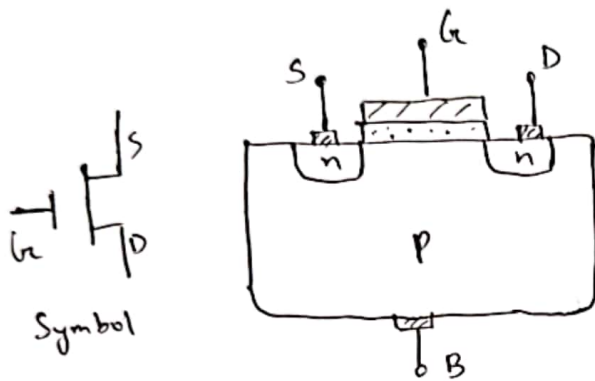


Fig: Enhancement Type nmos

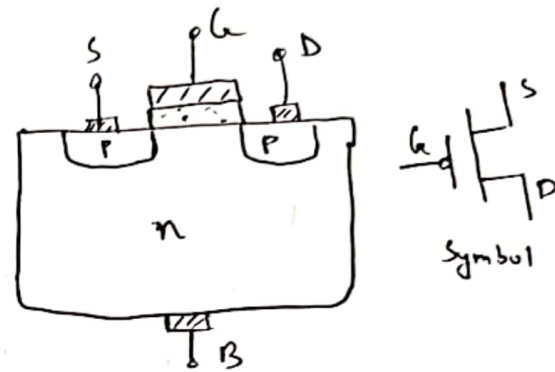


Fig: Enhancement Type pmos

Enhancement type nmos:

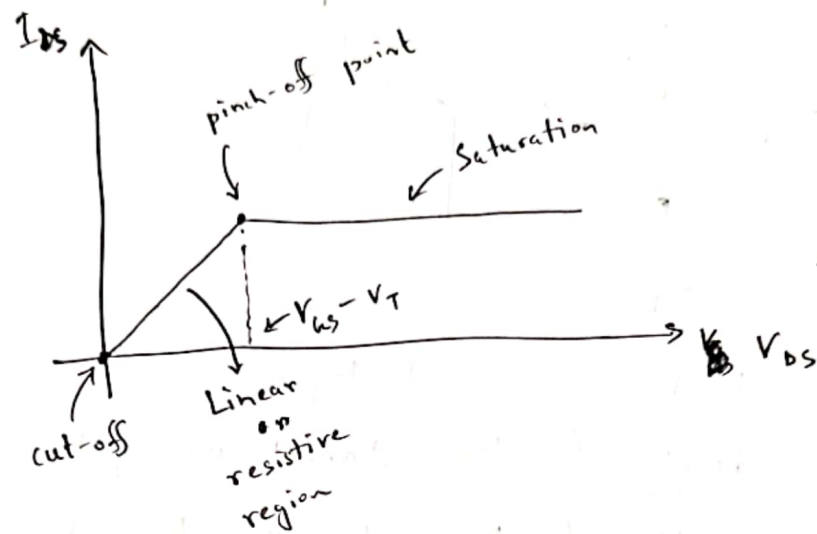
In order to make current flow from D to S channel has to be created between S to D by applying proper voltage (V_{GS}) between G & S.

The minimum gate to source voltage (V_{GS}) that is needed to create the channel is called the threshold voltage (V_T).

If $V_{GS} > V_T \rightarrow$ channel will be created

for nmos, V_T is (+ve)

I-V characteristics graph of enhancement type nMOS:



$V_{GS} < V_T \rightarrow$ no channel
 $I_{DS} = 0$

} cut-off

$V_{GS} > V_T \rightarrow$ channel will be created
 $V_{DS} = 0$
 $I_{DS} = 0$

} cut-off
 (the initial state of Linear region)

$V_{GS} > V_T$
 $0 < V_{DS} < (V_{GS} - V_T)$
 $I_{DS} > 0$

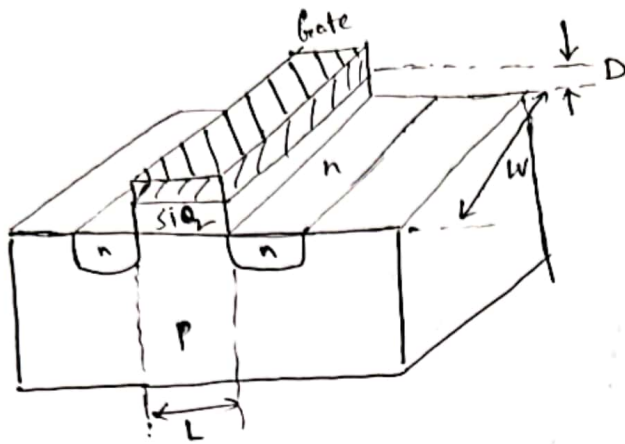
} Linear or resistive region

$V_{GS} > V_T$
 $V_{DS} = (V_{GS} - V_T)$
 $I_{DS} > 0$

} pinch-off point
 (end of linear region & starting point of saturation region)

$V_{GS} > V_T$
 $V_{DS} > (V_{GS} - V_T)$
 $I_{DS} > 0$

} Saturation region



$D \rightarrow$ thickness of oxide layer

$L \rightarrow$ length of the channel or gate

$W \rightarrow$ width of the gate or channel

In Linear region,

$$D \text{ to } S \text{ current, } I_{DS} = \frac{\epsilon \mu_n}{D} \cdot \frac{W}{L} \cdot \left[(V_{GS} - V_T) V_{DS} - \frac{V_{DS}^2}{2} \right]$$

$\epsilon \rightarrow$ permittivity of oxide layer

$\mu_n \rightarrow$ mobility of electron

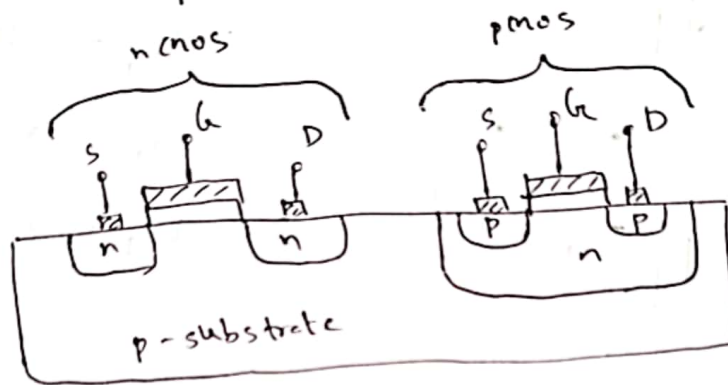
$\frac{W}{L} \rightarrow$ aspect ratio

In saturation region,

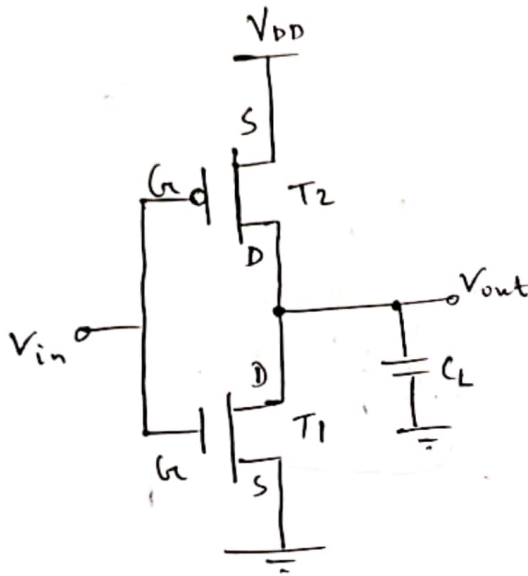
$$D \text{ to } S \text{ current, } I_{DS} = \frac{\epsilon \mu_n}{2D} \cdot \frac{W}{L} \cdot (V_{GS} - V_T)^2$$

CMOS (Complementary Metal Oxide Semiconductor)

combination of pMOS and nMOS in a single IC
~~normal~~ normally a single IC contains symmetrical (complementary)
pMOS - nMOS pairs



CMOS Inverter Design (NOT gate)



$T_1 \rightarrow \text{nMOS}$

$T_2 \rightarrow \text{pMOS}$

$$V_{Tp} = -1\text{V}$$

$$V_{Tn} = 1\text{V}$$

$$V_{DD} = 2.5\text{V}$$

$V_{in} \rightarrow \text{HIGH (2.5V)}$

For T_1 ,

$$V_{in} = V_{GS} = 2.5\text{V}$$

$$V_{GS} > V_{Tn}$$

$\therefore T_1$ is ON

For T_2 ,

$$V_{SG} = V_{DD} - V_{in}$$

$$= (2.5 - 2.5)\text{V}$$

$$= 0\text{V}$$

$$V_{SG} < |V_{Tp}|$$

$\therefore T_2$ is OFF

Output capacitor (C_L) will discharge

$$V_{out} = 0\text{V (Low)}$$

$V_{in} \rightarrow \text{LOW (0V)}$

For T_1 ,

$$V_{in} = V_{GS} = 0\text{V}$$

$$V_{GS} < V_{Tn}$$

$\therefore T_1$ is OFF

For T_2 ,

$$\begin{aligned} V_{SG} &= V_{DD} - V_{in} \\ &= (2.5 - 0)\text{V} \\ &= 2.5\text{V} \end{aligned}$$

$$V_{SG} > |V_{Tp}|$$

$\therefore T_2$ is ON

Output capacitor will charge through T_2

$$V_{out} = V_{DD} = 2.5\text{V}$$

Important properties of CMOS inverter:

- The high and Low output levels equal V_{DD} and GND, respectively.
- Ratioless design: which means that logic levels are not dependent on relative device sizes.
- In steady state, a finite resistance path exists between the output and either V_{DD} or GND.
- Input impedance is extremely high. Steady state i/p current is nearly zero. So, a single inverter can theoretically drive an infinite number of gates. (fan-out = infinite). However, increasing fan-out will increase propagation delay.
- No direct path exists between source and ground in steady state operation. Thus, no continuous current flow ~~lets~~ from V_{DD} to GND. So, static power dissipation is very less.

Input-Output Characteristics of CMOS Inverter (Voltage-transfer characteristics)

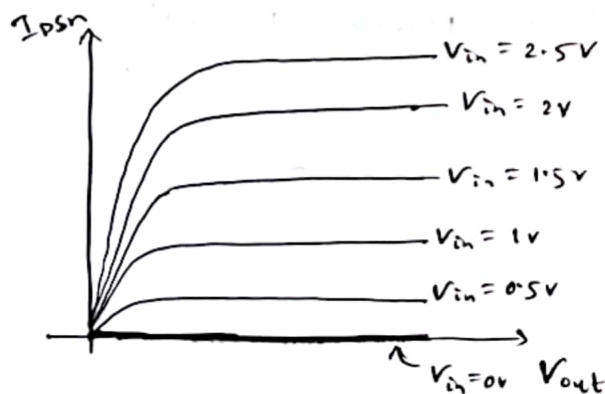
Steps to draw the graph:

- Sketch the I-V curve of the nMOS and pMOS transformed on a common co-ordinate set for different input voltages
- Superimpose the two ~~IV~~ I-V curves of nMOS & pMOS
- Find the operating points of the inverter from the intersecting points between the two curves for each input voltage level
- Plot the output voltage against the ~~ext~~ input voltage

Now,

Let, the variables associated with the common coordinate set be: V_{in} , V_{out} & I_{DSn} (Current through nMOS)

→ nMOS IV curve for different values of V_{in} :



$$V_{in} = V_{GSn}$$

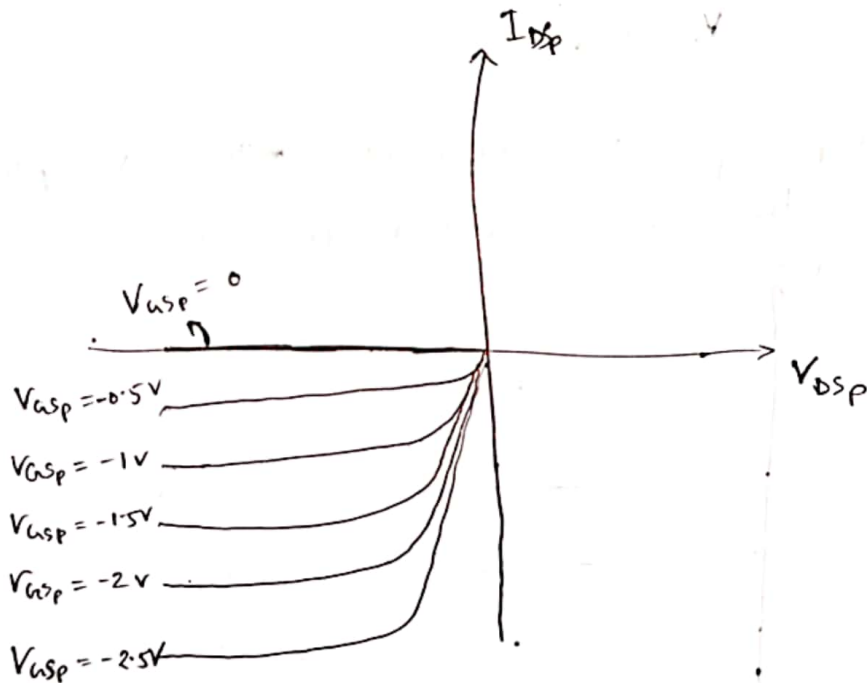
$$V_{out} = V_{DSn}$$

$$I_{DSn}$$

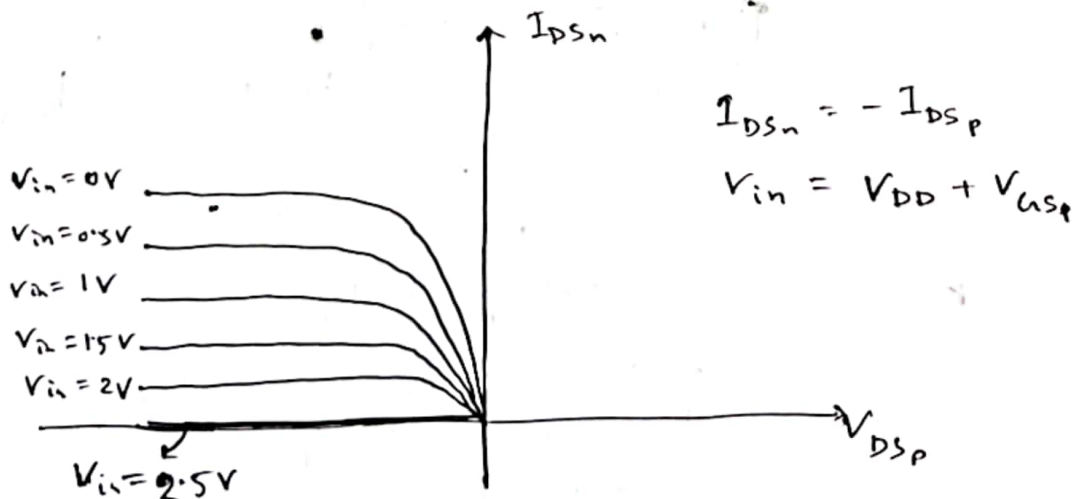
→ pmos IV curve can be transferred into the same coordinate set variables w.r.t. the following relations

$$\begin{array}{l|l} I_{Dsp} = -I_{Dsn} & I_{SDP} = I_{Dsn} \\ V_{bsp} = V_{in} - V_{DD} & V_{SGP} = V_{DD} - V_{in} \\ V_{Dsp} = V_{out} - V_{DD} & V_{SDP} = V_{DD} - V_{out} \end{array}$$

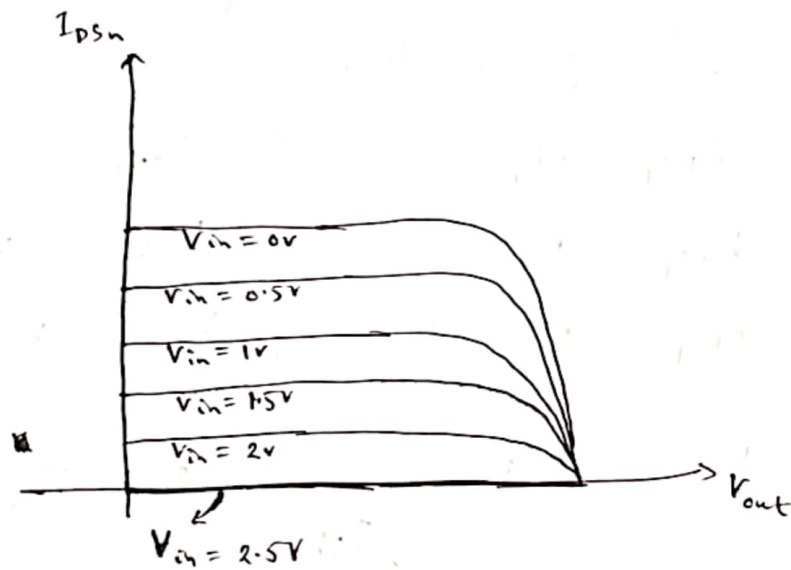
pmos IV curve in terms of I_{Dsp} , V_{Dsp} & V_{Gsp}



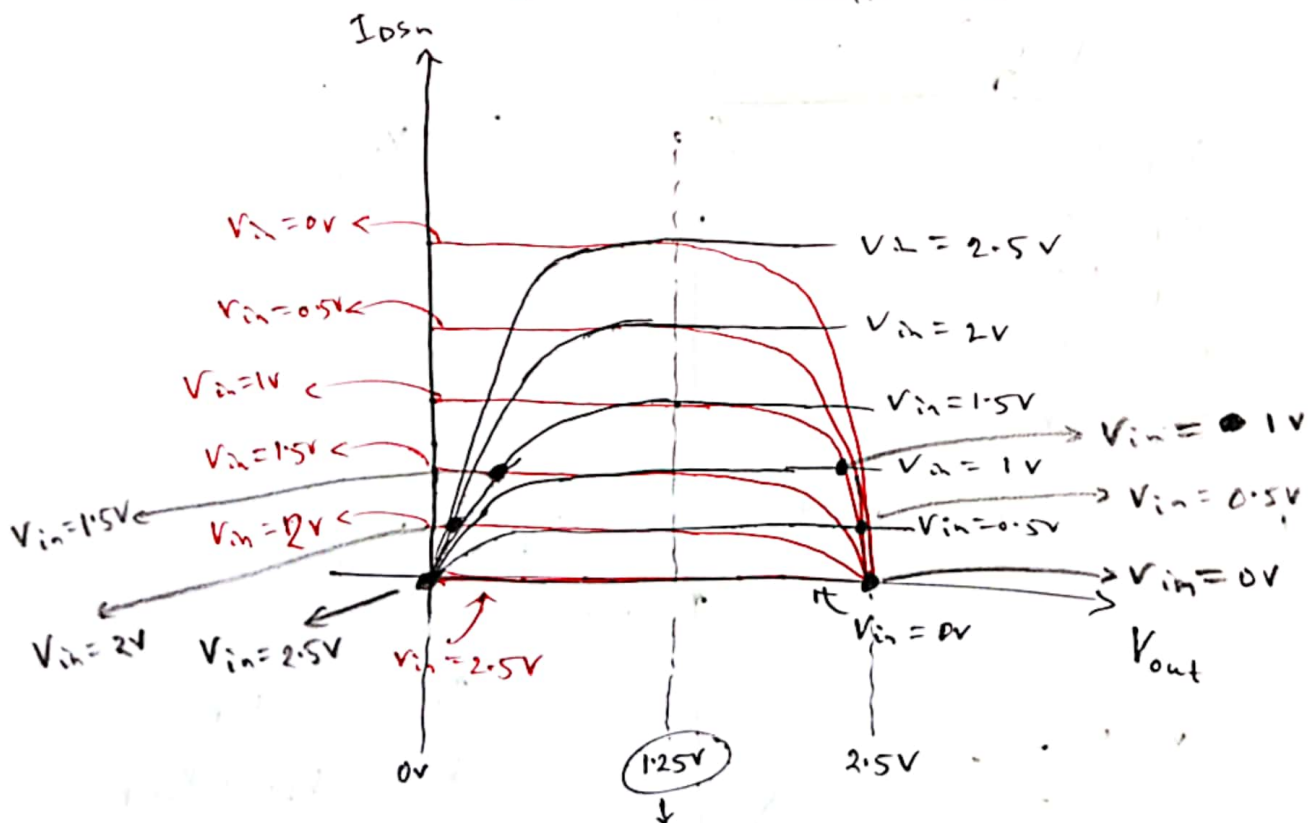
pmos IV curve in terms of I_{Dsn} , V_{Dsp} , V_{in}



pMOS IV curve in terms of I_{DSN} , V_{out} , V_{in}



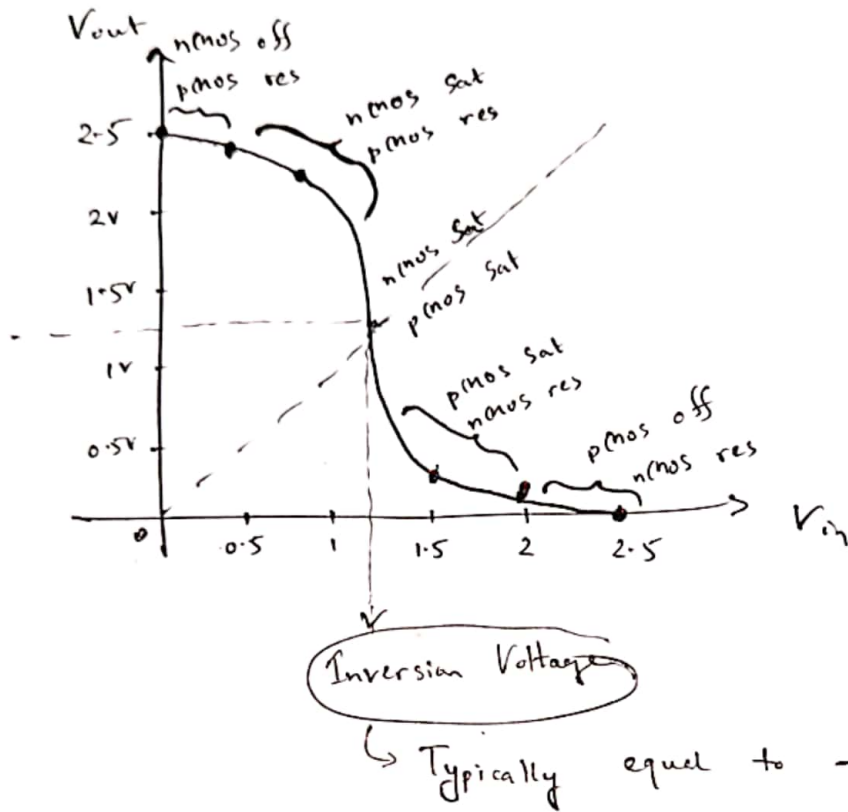
→ Superimposing IV curves of nMOS & pMOS drawn in the same co-ordinate set



Inversion Voltage

nMOS & pMOS interchange their mode of operation w.r.t this voltage

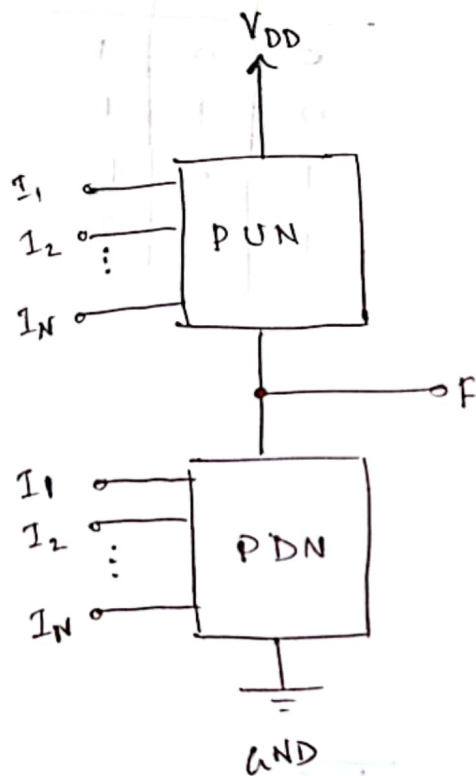
Input - Output Characteristic graph



Combinational Logic Gates using CMOS

Static CMOS Design

→ Static CMOS gate is a combination of two networks : pull-up network (PUN)
pull-down network (PDN)



PUN → provides a connection between output (F) and V_{DD} when F is supposed to be HIGH

PDN → provides a connection between output (F) and GND when F is supposed to be LOW

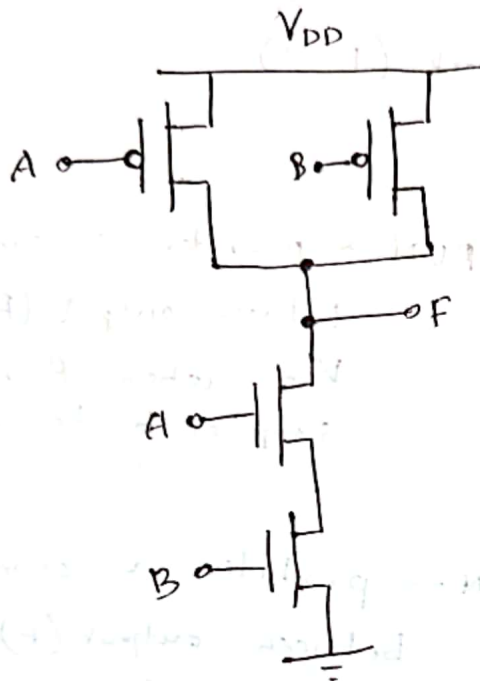
At steady state only one of the networks between PUN & PDN conducts

→ nMOS devices are normally used in the ~~PUN~~ PDN

→ pMOS devices are normally used in the ~~PDN~~ PUN

Two-Input NAND Gate:

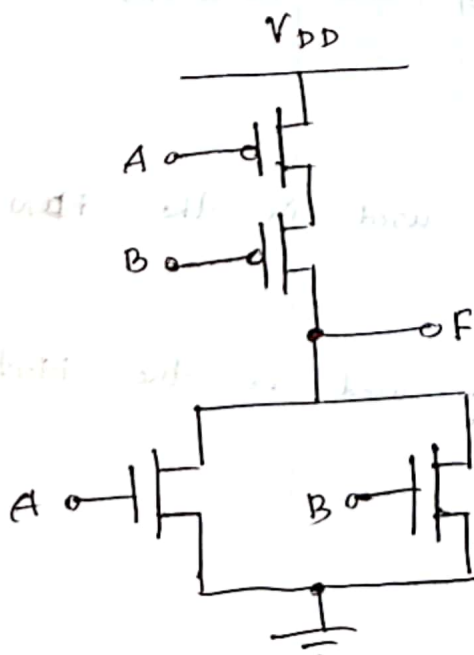
Boolean Expression, $F = \overline{A \cdot B}$



A	B	F
0	0	1
0	1	1
1	0	1
1	1	0

Two-Input NOR Gate:

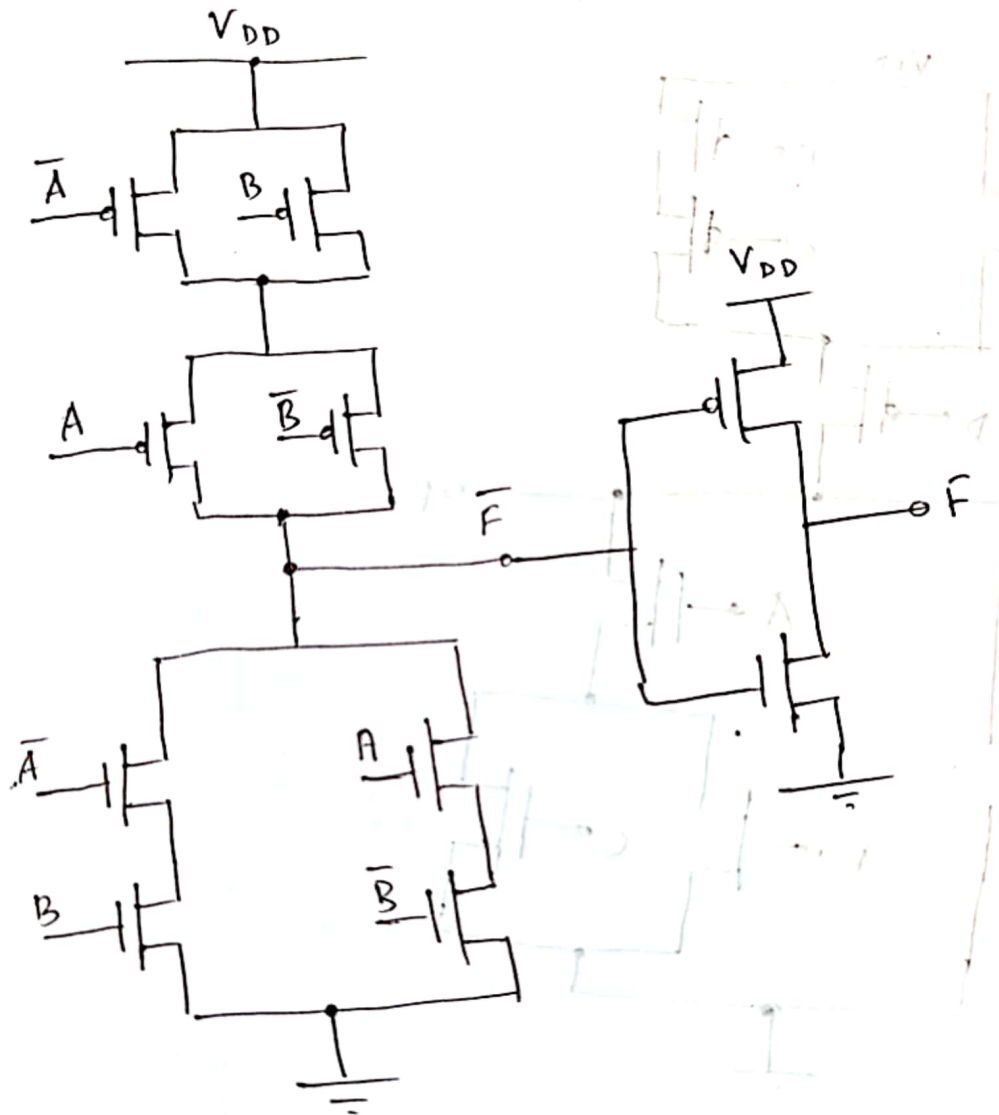
Boolean Expression, $F = \overline{A + B}$



A	B	F
0	0	1
0	1	0
1	0	0
1	1	0

XOR Gate

$$F = \bar{A}B + A\bar{B}$$



XOR Gate:

$$F = \bar{A}B + A\bar{B}$$

$$\therefore \bar{\bar{F}} = F = \overline{AB + \bar{A}\bar{B}}$$

$$\bar{F} = \overline{\bar{A}B + A\bar{B}}$$

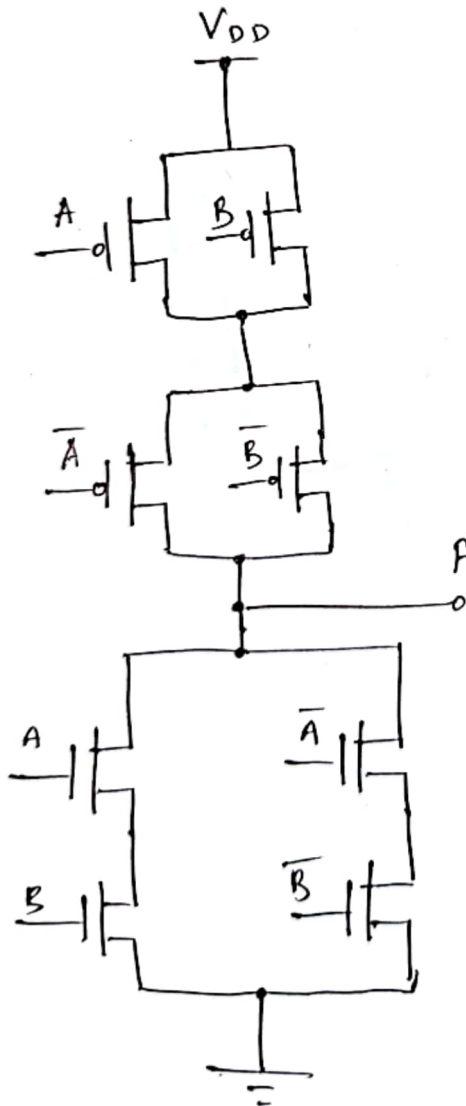
$$= \overline{(\bar{A} \cdot B)} \cdot \overline{(A \cdot \bar{B})}$$

$$= (\bar{\bar{A}} + \bar{B}) \cdot (\bar{A} + \bar{\bar{B}})$$

$$= (A + \bar{B}) \cdot (\bar{A} + B)$$

$$= A \cdot \bar{A} + A B + \bar{A} \bar{B} + \bar{B} B$$

$$= AB + \bar{A}\bar{B}$$



Example :

$$F = \overline{D + A \cdot (B + C)}$$

